

10644954_CLS

Most Frequently Occurring Classifications of Patents Returned
From A Search of 10644954 on July 28, 2004

Original Classifications

9	378/34
6	378/119
5	250/492.2
2	355/67
2	359/366
2	359/857

Cross-Reference Classifications

10	378/34
7	355/67
4	355/53
4	378/119
3	250/492.1
3	250/492.3
3	359/859
3	378/145
3	378/146
3	378/147
3	378/35
3	378/84
3	378/85
2	250/492.2
2	250/504R
2	257/E21.035
2	257/E21.279
2	359/366
2	359/858
2	359/861
2	378/143
2	430/396

Combined Classifications

19	378/34
10	378/119
9	355/67
7	250/492.2
5	355/53
4	250/492.1
4	359/366
4	359/859
4	378/85
3	250/492.3
3	359/857

10644954_CLS

3 359/858
3 378/145
3 378/146
3 378/147
3 378/35
3 378/84
2 250/492.22
2 250/504R
2 257/E21.035
2 257/E21.279
2 355/69
2 356/520
2 359/861
2 378/143
2 430/296
2 430/30
2 430/311
2 430/396

10644954_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10644954 on July 28, 2004

19	378/34	(9 OR, 10 XR)
	Class 378	: X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
	378/1	SPECIFIC APPLICATION
	378/34	.Lithography
10	378/119	(6 OR, 4 XR)
	Class 378	: X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
	378/119	SOURCE
9	355/67	(2 OR, 7 XR)
	Class 355	: PHOTOCOPYING
	355/18	PROJECTION PRINTING AND COPYING CAMERAS
	355/67	.Illumination systems or details
7	250/492.2	(5 OR, 2 XR)
	Class 250	: RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
5	355/53	(1 OR, 4 XR)
	Class 355	: PHOTOCOPYING
	355/18	PROJECTION PRINTING AND COPYING CAMERAS
	355/53	.Step and repeat
4	250/492.1	(1 OR, 3 XR)
	Class 250	: RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
4	359/366	(2 OR, 2 XR)
	Class 359	: OPTICS: SYSTEMS
	359/362	COMPOUND LENS SYSTEM
	359/364	.With curved reflective imaging element
	359/365	..Two or more in a series
	359/366	...Concave,-convex-combination
4	359/859	(1 OR, 3 XR)
	Class 359	: OPTICS: SYSTEMS
	359/838	MIRROR
	359/850	.Plural mirrors or reflecting surfaces
	359/857	..With successive reflections
	359/858	...Including curved mirror surfaces in series
	359/859With concave and convex mirrors in series

10644954_CLSTITLES

4 378/85 (1 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/70 .Diffraction, reflection, or scattering analysis
378/82 ..Spatial energy dispersion
378/84 ...Monochromator or focusing device
378/85With plural dispersing elements

3 250/492.3 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation

3 359/857 (2 OR, 1 XR)
Class 359 : OPTICS: SYSTEMS
359/838 MIRROR
359/850 .Plural mirrors or reflecting surfaces
359/857 ..With successive reflections

3 359/858 (1 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/838 MIRROR
359/850 .Plural mirrors or reflecting surfaces
359/857 ..With successive reflections
359/858 ...Including curved mirror surfaces in series

3 378/145 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL

3 378/146 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL
378/146 .Scanner

3 378/147 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL
378/147 .Collimator

3 378/35 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/34 .Lithography

10644954_CLSTITLES
..Pattern mask

3 378/84 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/70 .Diffraction, reflection, or scattering
analysis
378/82 ..Spatial energy dispersion
378/84 ...Monochromator or focusing device

2 250/492.22 (1 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.22 ..Pattern control

2 250/504R (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/493.1 RADIANT ENERGY GENERATION AND SOURCES
250/503.1 .With radiation modifying member
250/504R ..Ultraviolet or infrared source

2 257/E21.035 (0 OR, 2 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE

OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF

PARTS THEREOF (EPO)

257/E21.002 .Manufacture or treatment of semiconductor device (EPO)

257/E21.023 ..Making mask on semiconductor body for further photolithographic processing (EPO)

257/E21.033 ...Comprising inorganic layer (EPO)

257/E21.035Characterized by their composition, e.g., multilayer masks, materials (EPO)

2 257/E21.279 (0 OR, 2 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE

SOLID-STATE DEVICES OR OF OR TREATMENT OF SEMICONDUCTOR OR

PARTS THEREOF (EPO)

257/E21.002 .Manufacture or treatment of semiconductor device (EPO)

257/E21.04 ..Device having at least one potential-jump

10644954_CLSTITLES

barrier or surface barrier, e.g.,
 PN junction, depletion
 (EPO) layer, carrier concentration layer

257/E21.085 ...Device having semiconductor body comprising
 Group IV elements or Group III-V co-
 mpounds with or without
 (EPO) impurities, e.g., doping materials

257/E21.211Treatment of semiconductor body using
 process other than deposition of sem-
 iconductor material on
 f impurity material, or
 radiation treatment (EPO)

257/E21.214To change their surface-physical
 characteristics or shape, e.g., etchi-
 ng, polishing, cutting
 (EPO)

257/E21.24To form insulating layer thereon, e.g.,
 for masking or by using photolithogra-
 hic technique (EPO)

257/E21.266Inorganic layer (EPO)
 257/E21.271Composed of oxide or glassy oxide or
 oxide based glass (EPO)
 257/E21.274Deposition from gas or vapor (EPO)
 257/E21.278Deposition of silicon oxide (EPO)
 257/E21.279On silicon body (EPO)

2 355/69 (1 OR, 1 XR)
 Class 355 : PHOTOCOPYING
 355/18 PROJECTION PRINTING AND COPYING CAMERAS
 355/67 .Illumination systems or details
 355/69 ..Electricity to lamp controlled

2 356/520 (1 OR, 1 XR)
 Class 356 : OPTICS: MEASURING AND TESTING
 356/450 BY LIGHT INTERFERENCE (E.G., INTERFEROMETER)
 356/520 .Having shearing

2 359/861 (0 OR, 2 XR)
 Class 359 : OPTICS: SYSTEMS
 359/838 MIRROR
 359/850 .Plural mirrors or reflecting surfaces
 359/857 ..With successive reflections
 359/861 ...With three or more successive reflections

10644954_CLSTITLES

2 378/143 (0 OR, 2 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/119 SOURCE
378/143 .Target

2 430/296 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR
R PRODUCT
430/296 .Electron beam imaging

2 430/30 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST
OR MEASUREMENT

2 430/311 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR
R PRODUCT
430/311 .Making electrical device

2 430/396 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/396 EFFECTING FRONTAL RADIATION MODIFICATION DURING

G
ING, ETC.